

School

IIT2010 will be preceded by a 3-day school taught by an international instructor corps of experts.

Dates

June 3-5, 2010

Place

Miyako Messe (Kyoto International Exhibition Hall)

Textbook

An updated version of the schoolbook, "Ion Implantation: Science and Technology", will be provided to all of the students.

Registration & Fee

On-line registration is also available for IIT School as well as Conference. The fee for the School is JPY 50,000 and 30,000 for regular and student participants, respectively. In addition, a discount rate is offered to the students to attend both IIT School and Conference (see also 'Registration Fee' section).



International Committee

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Conference Co-Chairs

Jiro Matsuo (Kyoto University)
Masataka Kase (Fujitsu Microelectronics Ltd.)
Masao Naito (Nissin Ion Equipment Co. Ltd.)
Michiro Sugitani (SEN Corp.)

Secretariat

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IIT2010

18th International Conference on Ion Implantation Technology



June 6-11, 2010

**Kyoto University Clock Tower
Centennial Hall
Kyoto, Japan**

<http://www.iit2010.org/>

Innovations in Ion Implantation

The International Conference on Ion Implantation Technology (IIT) is a biannual international conference on ion implantation technology and is one of the largest conferences on ion beam material processing technology. The 18th IIT conference will be held in June 2010, at Kyoto.

Conference Topics

Front line of Implant Technologies

Advanced Implant System, 32/22nm Device Manufacturing, 450mm Wafer, Process Control and Yield, Plasma Doping, Cluster Ions,

Challenges for Non-planar Structure & Novel Device Technology

Conformal Doping, High Tilt Angle Implant, Advanced Anneal, S/D Engineering, Co-Implantation.....

Material Science

Ion-Solid Interaction, Modeling and Simulation, Defect Formation and Elimination, Damage Control, Diffusion of Dopant and Other atoms, III-V (GaAs, ...), Metrology, Nano Structure and Synthesis, Bio-Materials,

New Horizons in Ion Implantation

Power Devices (SiC, GaN, ...), Photovoltaics, FPD, MEMS, Non-Doping and Novel Application,

Plenary Speakers

Devendra Sadana (IBM)

CMOS Scaling Beyond 22 nm: Issues and Challenges

Katsuhiro Tsukamoto (Renesas)

Evolution of Ion Implantation Technology and Its Contribution to Semiconductor Industry

Isao Yamada (Kyoto University)

Japan's Contributions to Ion Beam Technologies

Venue

IIT2010 Conference (June 6-11, 2010)

Kyoto University Clock Tower Centennial Hall

IIT2010 School (June 3-5, 2010)

Miyako Messe (Kyoto International Exhibition Hall)

Important Dates

February 14, 2010	Abstract deadline
April 20, 2010	Early registration deadline
May 31, 2010	On-line registration and hotel reservation close
June 3-5, 2010	IIT School
June 6-11, 2010	IIT2010 Conference

Registration Fee

The registration should be done through the IIT2010 web page. The registration fees are JPY 65,000 for a regular participant and JPY 30,000 for a student, respectively. They cover an abstract book, manuscript submission, one copy of the conference proceedings and the social programs (welcome reception, excursion and banquet). The accompanying person registration fee only includes social programs. Details of a more extensive "partners program" will be available on the IIT2010 website. Early registration rates are available before **April 20, 2010**.

	Before April 20, 2010	After April 21, 2010
Regular		
Conference only	JPY 65,000	JPY 75,000
School only	JPY 50,000	JPY 50,000
Conference & School	JPY 115,000	JPY 125,000
Student		
Conference only	JPY 30,000	JPY 40,000
School only	JPY 20,000	JPY 20,000
Conference & School	JPY 40,000	JPY 50,000
Accompany person	JPY 10,000	JPY 15,000

Call for Papers

IIT2010 program committee widely calls for valuable papers on recent developments of ion implantation technology - from fundamental research to industrial application.

Deadline

The deadline of abstract submission is **February 14, 2010**. Abstract should be submitted on IIT2010 web page.

Abstract preparation

The presentation abstract for IIT2010 should be written in English. The length of abstract should not exceed A4 (21.0mm×29.7mm) 1 page with margins of 35 mm from the top and 30 mm from the other sides. The abstract starts with, "Title of presentation", "Author list" and "Authors" affiliations, address and e-mail address of presenting author". The body of abstract should be in 10 points, which may include tables, figures and references. Especially, it is highly recommended to include table and/or figures attracting participants. The abstract must be translated in PDF format on submission.

For the detail of abstract preparation, please refer 'Call for papers' section in <http://www.iit2010.org/>.

Awards

The presenter who is younger than 36 years old, or who is university student, may nominate himself/herself to 'Young Investigator Award' or 'Student Award'. These awards will be determined based on submitted abstracts by a panel from IIT international and program committee. In order to apply for these awards, select suitable options on submitting abstract via the IIT2010 web page.